

Title (en)
Low field electrophotographic process.

Title (de)
Elektrophotographisches Niederfeldverfahren.

Title (fr)
Procédé électrophotographique à champ bas.

Publication
EP 0173620 A1 19860305 (EN)

Application
EP 85401622 A 19850809

Priority
US 64260384 A 19840820

Abstract (en)
An electrophotographic process in which a photoconductive insulating element, comprising a layer of intrinsic hydrogenated amorphous silicon in electrical contact with a layer of doped hydrogenated amorphous silicon, is electrostatically charged to a low level of surface voltage, such as, for example, a level of ten volts, provides an advantageous combination of very high electrophotographic sensitivity with minimal electrical noise.

IPC 1-7
G03G 13/22; **G03G 13/02**; **G03G 13/04**; **G03G 5/04**; **G03G 5/082**; **G03G 5/14**

IPC 8 full level
G03G 15/05 (2006.01); **G03G 5/082** (2006.01); **G03G 13/26** (2006.01)

CPC (source: EP)
G03G 5/08221 (2013.01)

Citation (search report)

- US 4265991 A 19810505 - HIRAI YUTAKA, et al
- US 4461819 A 19840724 - NAKAGAWA KATSUMI [JP], et al
- US 4443529 A 19840417 - KANBE JUNICHIRO [JP], et al
- US 4409308 A 19831011 - SHIMIZU ISAMU [JP], et al

Designated contracting state (EPC)
BE DE FR GB IT

DOCDB simple family (publication)
EP 0173620 A1 19860305; **EP 0173620 B1 19890426**; CA 1249476 A 19890131; DE 3569843 D1 19890601; JP S6159353 A 19860326

DOCDB simple family (application)
EP 85401622 A 19850809; CA 481644 A 19850515; DE 3569843 T 19850809; JP 18059685 A 19850819